

-	Pd (scfmc3)	Py-Nb (scfmh2)	Co-Nb (scfmi4)
sub cleaning	sonicate in acetone/IPA	sonicate in acetone/IPA	sonicate in acetone/IPA
markers	mask aligner (S1813), sputter Cr/Mo	mask aligner (S1813), sputter Cr/Mo	mask aligner (S1813), sputter Mo
catalyst	SEM (PMMA), drop cast from water solution	SEM (PMMA), drop cast from water solution	mask aligner (NR9), UV/OZ clean, drop cast from water solution
cnt growth	15 minute pretreatment, 300 Ar/300 H2/ 740 CH4, 12 minute growth, small tube	1 hr pretreatment, 350 Ar/350 H2/700 CH4, 10 minutes growth	1 hr pretreatment, 350 Ar/350 H2/700 CH4, 10 minutes growth
leads/bonding pads	SEM (PMMA), Cr/Au evaporated (new)	SEM (PMMA), Cr/Au evaporated (old)	SEM (PMMA) Cr/Au evaporated (old)
cnt contacts	SEM (PMMA/room temp/scale dose), sputter Pd	SEM (PMMA/room temp/scale dose), evaporate Py (old), sputter Ti/Nb	SEM (PMMA/room temp/scale dose), sputter Co/Au, sputter Ti/Nb
anneal	no	yes, 500 Ar/500 H2/325C/3hrs	no
leads measured	Pd-Pd	Py-Nb, Nb-Nb	Co-Co
measurement	dunker/Oxford magnet/DC (DAQ/Ithaco)	Reich He3/Reich magnet/DC (DAQ/Kepco/Ithaco)	Reich He3/Reich magnet/AC (DAQ/SR830/Ithaco), dunker/Reich magnet/AC (DAQ/SR830/Ithaco)
drift/stray cap	no	yes	yes

scfmi4 is still alive and in the dunker.

